ALD 2016 Ireland

Robert D. Clark
Sr. Member of the Technical Staff
Tokyo Electron, Inc.

Robert Clark received his Ph.D. in Chemistry in 2000 from U.C. Irvine and holds B.S. and M.S. Chemistry degrees from Virginia Tech. He joined Air Products and Chemicals in 2000 where he worked as a Principal Research Chemist developing ALD High K and Metal Gate precursors including the first ALD High K Gate Dielectric precursor used in high volume manufacturing.

In 2006 he Joined Tokyo Electron at the TEL Technology Center, America (TTCA), LLC in Albany, New York and relocated to California in 2010. He is currently an elected Senior Member of the Technical Staff for Tokyo Electron U.S. His research spans FEOL and BEOL integration and devices including advanced device integration, ALD, CVD, patterning, functional patterning/integration films, selective depositions, ALE, advanced cleans, surface preparations, FinFETs, Nanowire FETs, High K/Metal Gate Films, advanced contacts, alternative channel materials, resistive memories and DRAM. He chaired SRC Device Sciences in 2013 and is currently on the ITRS Wafer and Environmental Control Committee.

He is a member of several conference committees including SISC, VLSI-TSA, and CMC. He holds more than 35 issued U.S. patents and has authored or co-authored more than 90 publications and conference presentations including numerous invited presentations and papers.